Attorney Docket: MXIC 1553-3

## EXPRESS MAIL LABEL NO. EV102698707US DATED: 15 AUGUST 2003

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Chih C. YEH et al.

Application No. \_\_\_\_

Filed: 15 August 2003 (herewith)

Customer No. 22470

Title: Method for Programming

**Programmable Eraseless Memory** 

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

It is requested that the information identified in this statement be considered by the Examiner and made of record in the above-identified application. This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in 37 C.F.R. 1.56.

Enclosed with this statement is a Form PTO-1449. The Examiner is requested to initial the form and return it to the undersigned in accordance with M.P.E.P. 609.

[A] This statement should be considered under 37 C.F.R. 1.97(b) because it is being filed within three months of the filing date of an application other than a continued prosecution application under 37 C.F.R. 1.53(d).

Respectfully submitted, Haynes Beffel & Wolfeld LLP

Date: 15 August 2003

Mark A. Haynes, Reg. No. 30,846

Haynes Beffel & Wolfeld LLP P.O. Box 366 Half Moon Bay, CA 94019 Ph. (650) 712-0340 Fax (650) 712-0263

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PTO/SB/08A (08-00)

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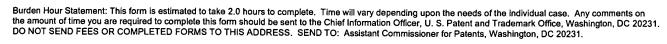
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		N DIO		Application Number		
			CLOSURE	Filing Date	15 August 2003	
STA	TEMENT	BY AF	PLICANT	First Named Inventor	Chih C. YEH et al.	
				Group Art Unit		
	(use as many s	sheets as n	ecessary)	Examiner Name		
Sheet 1 of 2		Attorney Docket Number	MXIC 1553-3			

U.S. PATENT DOCUMENTS								
Examiner Initials*	Cite No. <sup>1</sup>	Number (ii	nd Code <sup>2</sup>	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
	Al	4.442.507		Roesner	4/10/1984			
	A2	5,536,968		Crafts et al.	7/16/1996			
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FOREIGN PATENT DOCUMENTS									
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	Cite No. <sup>1</sup>	Office <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)	Applicant of Cited Document	Cited Document MM-DD-YYYY	Where Relevant Passages or Relevant Figures Appear	Te	
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<sup>&</sup>lt;sup>1</sup> Unique citation designation number. <sup>2</sup> See attached Kinds of U.S. Patent Documents. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.



<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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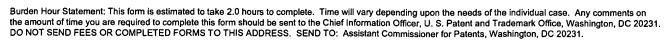
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				Application Number		
INFC	RMAHO	N DIS	CLOSURE	Filing Date	15 August 2003	
STATEMENT BY APPLICANT				First Named Inventor	Chih C. YEH et al.	
		,	. 2.0,	Group Art Unit		
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		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	C1	C. de GRAAF et al., "A Novel High-Density Low-Cost Diode Programmable Read Only Memory" Philips Research Labs., Prof. Holstlaan 4, 5656AA Eindhoven, The Netherlands, 1996 IEDM, pps. 189-192.	
	C2	M. JELINEK et al., "Hybrid PLD Technique for Nitrogen Rich CNx Layers", Lasers and Electro-Optics Europe, 2000. Conf. Digest. 2000 Conf. on, 10-15 Sept 2000, 1 page.	
	C3	B. LINDER et al., "Growth and Scaling of Oxide Conduction After Breakdown", 41st Annual Int'l Reliability Physics Symposium, Dallas, TX, 2003, pp. 402-405.	
	C4	S. ROSSNAGEL et al., "From PVD to CVD to ALD for Interconnects and Related Applications", Interconnect Technology Conf., 2001. Proceedings of the IEEE 2001 Int'l, 4-6 June 2001, pp. 3-5.	
	C5	X.W WANG et al., "Ultra-Thin Silicon Nitride Films on Si by Jet Vapor Deposition", VLSI Technology, Systems and Applications, 1995, Proceedings of Technical Papers, 1995 International Symposium on, 31 May-2 June 1995, pp. 49-52.	

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Examiner		Date	
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